

Automated Introduction Semiconductor Chemicals

Fluoronetic prepFASTS Ultraclean Sample Introduction System

prep*FAST* S[™]

Automated Sample Preparation and Introduction System for Semiconductor Applications

The prep*FAST* S has revolutionized the way ultrapure semiconductor grade chemicals are analyzed with ICPMS detection. The prep*FAST* S utilizes syringe-driven flows of UPW, semiconductor grade acids, and standard solution to automate both sample dilutions and standard curve generation. It eliminates manual handling of samples to deliver sub-ppt detection limit capabilities.

prepFAST S Autocalibration

The prep*FAST* S automatically prepares calibration curves for over 40 elements controlled in semiconductor manufacturing processes. Calibrations are generated by automatically diluting an enclosed multielement stock standard. Automation with the high-purity prep*FAST* S achieves low to sub-ppt calibrations.



High Purity Automation with PPT/PPQ results

Automation

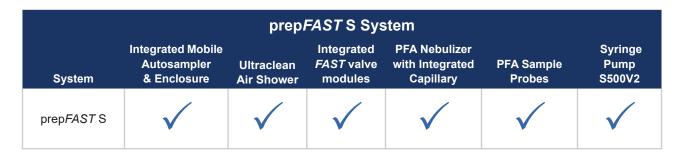
- Automatic external and MSA calibrations
- Automated sample sensing
 - accounts for viscosity and automatically adjusts timing
 - detects and injects the sample and triggers the ICPMS
- Automated syringe-driven sample introduction
 - Sample loading
 - Sample preparation
 - Inline dilution
 - Acid addition

Ultraclean

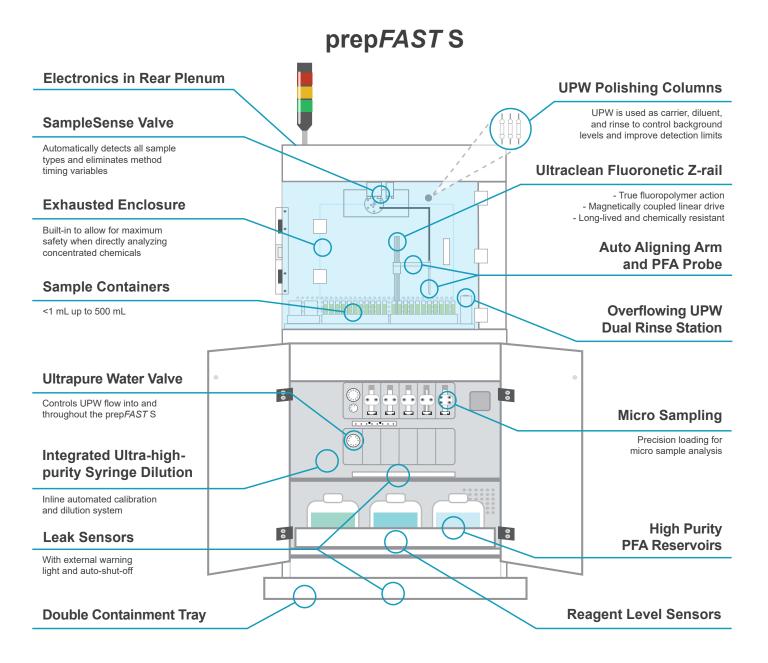
- Ultraclean sample preparation
- Integrated ultraclean sample environment
 - Includes ultraclean fluoronetic autosampler and air shower
 - Options include:
 - ULPA (Ultrapure air) filter
 - Sample racks for PFA containers (<1 mL to 500 mL)
- Continuously-flowing high purity UPW rinse (user-supplied UPW)
- UPW polishing columns for low background

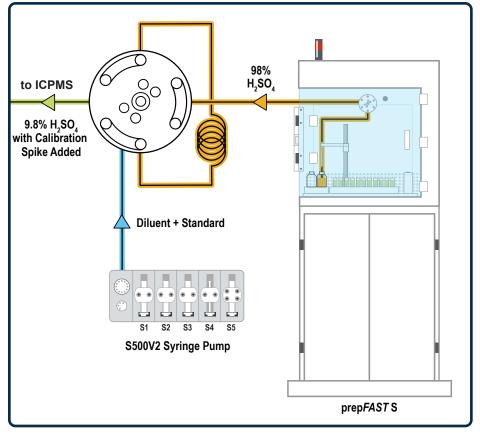
PPT/PPQ Results

- · Capability to analyze all semiconductor grade chemicals
- PPT/PPQ detection limits for all semiconductor elements



Pure Automation





prepFAST S Inline Dilution of Semiconductor-grade Chemicals

The prep*FAST* S allows dilution by volume or weight for all semiconductor-grade chemicals. Metals are quantified using automated inline MSA or external calibration. Automated direct analysis of concentrated chemicals eliminates sample contamination caused by manual dilution into a secondary container.

Diagram showing 10x inline dilution of concentrated H_2SO_4 with prepFAST S.

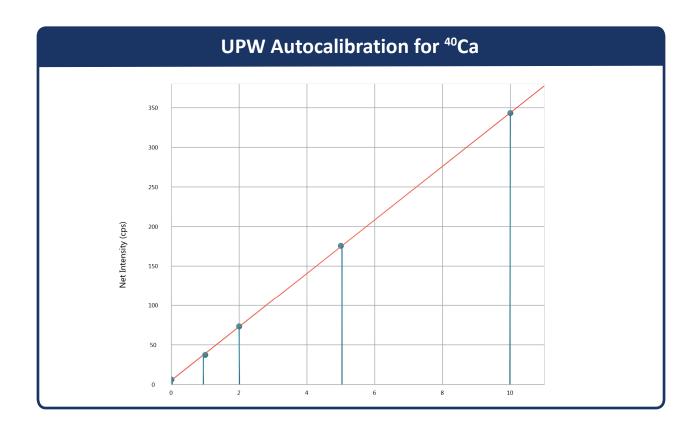
| Examples of Semiconductor Chemicals Analyzed at the ppt Level with prepFAST S | | | | | | | |
|---|------------------------|------------------------------------|----------------------|--------|---------------|-----------------------------------|--|
| Acids | 98% H_2SO_4 | 89% H ₃ PO ₄ | 70% HNO ₃ | 49% HF | 35% HCI | 30% H ₂ O ₂ | |
| Bases | 22% NH ₄ OH | 2.38% TMAH | 25%TMAH | KOH | | | |
| Organics | IPA | PGMEA/PGME | Photoresist | NMP | Butyl Acetate | Cyclohexanone | |

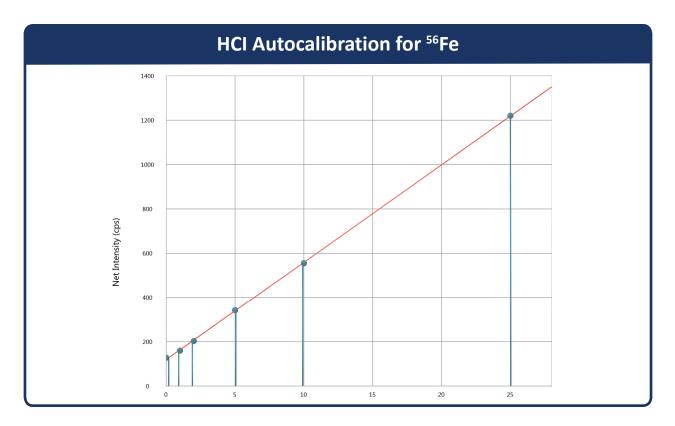
This table contains only a partial list of chemicals which can be analyzed using prepFAST S.

Detection Limits

| Example of Detection Limits in Non-cleanroom environment | | | | | | |
|--|----------|-------------------|----------|--|--|--|
| Element | DL (ppt) | Element | DL (ppt) | | | |
| ⁷ Li | 0.02 | ⁷² Ge | 0.04 | | | |
| ⁹ Be | 0.007 | ⁷⁵ As | 0.2 | | | |
| ¹¹ B | 0.9 | ⁸⁵ Rb | 0.008 | | | |
| ²³ Na | 0.07 | ⁸⁸ Sr | 0.008 | | | |
| ²⁴ Mg | 0.01 | ⁹⁰ Zr | 0.004 | | | |
| ²⁷ AI | 0.03 | ⁹³ Nb | 0.002 | | | |
| ³⁹ K | 0.06 | ⁹⁵ Mo | 0.5 | | | |
| ⁴⁰ Ca | 0.4 | ¹¹¹ Cd | 0.07 | | | |
| ⁴⁸ Ti | 0.02 | ¹¹⁵ ln | 0.004 | | | |
| ⁵¹ V | 0.1 | ¹¹⁸ Sn | 0.05 | | | |
| ⁵² Cr | 0.1 | ¹²¹ Sb | 0.05 | | | |
| ⁵⁵ Mn | 0.009 | ¹³⁷ Ba | 0.04 | | | |
| ⁵⁶ Fe | 0.04 | ¹⁷⁸ Hf | 0.003 | | | |
| ⁵⁸ Ni | 0.01 | ¹⁸¹ Ta | 0.01 | | | |
| ⁵⁹ Co | 0.007 | ^{182}W | 0.01 | | | |
| ⁶⁰ Ni | 0.01 | ²⁰⁵ TI | 0.002 | | | |
| ⁶³ Cu | 0.03 | ²⁰⁸ Pb | 0.005 | | | |
| ⁶⁴ Zn | 0.04 | ²³² Th | 0.000 | | | |
| ⁷¹ Ga | 0.002 | ²³⁸ U | 0.003 | | | |

Autocalibration







www.icpms.com

© Elemental Scientific | 7277 World Communications Drive | Omaha, NE 68122 Tel: 402-991-7800 | sales@icpms.com | www.icpms.com